

Jacob, Rebecca (ASRC)

LC

401020

From: STIC-ILL
Sent: Monday, June 24, 2002 11:27 AM
To: Jacob, Rebecca (ASRC)
Subject: FW: ILL order

-----Original Message-----

From: Bates, Darcy
Sent: Monday, June 24, 2002 11:24 AM
T : STIC-ILL
Cc: Harrison, Jeff; Blalock, Derrick (ASRC); Hendrickson, Anne; Speckhard, Irina (ASRC); Magee, Thomas
Subject: ILL order

Hi,

We do not have the following item in STIC. Please order this item for Thomas Magee, CP4-4D23.

ILL Ordering Information

Date Needed<6-26-02>

Art Unit or Location <2811>

Telephone Number <305-5396>

Title: **Passivation of copper by silicide formation in dilute silane.**

Author(s): Hymes, S.; Murarka, S.P. (Rensselaer Polytech. Inst., Troy, NY, USA); Shepard, C.; Lanford, W.A.

Source: **Advanced Metallization for ULSI Applications (Formerly Workshop on Tungsten and Other Advanced Metals for ULSI Applications)**

Proceedings of the Conference Editor(s): Rana, V.V.S.; Joshi, R.V.; Ohdomari, I. Pittsburgh, PA, USA:

Mater. Res. Soc, 1992. p.425-31 of xv+580 pp. 6 refs.

Conference: Murray Hill, NJ, USA and Tokyo, Japan, 8-10 Oct 1991 and 28-30 Oct 1991

DT Conference Article

TC Experimental

CY United States

LA English

Thank you,

Darcy Bates

EIC 2800 Technical Information Specialist

U.S. Patent & Trademark Office

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WAW
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